

MB EVAP S/A[®]

STAND ALONE VACUUM DEPOSITION SYSTEM



The MB-EVAP S/A vacuum deposition system is a high quality, stand alone, research & development tool designed for all of your thin film requirements. The M.E.S.A. system comes standard as a 2 to 4 resistive source system with the capability to deposit in sequence or simultaneously and can also be configured to include RF or DC sputter sources as well as e-beam sources. Our design incorporates many of the high quality components used by similar suppliers while still allowing MBraun to offer our systems at a cost competitive price. MBraun can configure the M.E.S.A. system to meet your exact requirements in addition to offering a system designed for easy integration to an MBraun inert atmosphere glovebox system. Please contact MBraun for more information on this product.

Options include:

- 2 to 4 resistive sources
- RF or DC sputtering
- E-beam sources
- 500mm³ vacuum chamber
- Turbomolecular pump stacks
- Cryogenic pump stacks
- Rate & thickness monitoring
- Substrate heating & cooling
- Substrate rotation
- Source & substrate shutters



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ISO 9001-2000 Certified

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